Christina Porter has been a member of the research department at ASML since the beginning of 2019. She is a project leader working on next generation, scatterometry based metrology solutions. Christina has a Master's degree in electrical engineering from Princeton University and a Ph.D. in physics from the University of Colorado at Boulder, where she worked in the research group of Margaret Murnane and Henry Kapteyn. Her dissertation was on complex, EUV imaging reflectometry: pairing tabletop, high harmonic generation EUV light sources with angle resolved ptychography to achieve non-destructive, quantitative 3D imaging in reflection geometries. She joined ASML with the dream of carrying similar technology through to its real world application in the semiconductor industry, where increasingly 3D nanoscale devices require revolutionary metrology techniques to keep up with Moore's law.